

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 6,822,727 B2
DATED : November 23, 2004
INVENTOR(S) : Shinichi Shima

Page 1 of 4

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title page,

Item [57], **ABSTRACT**, delete the current abstract and insert the following therefor:

-- An exposure apparatus includes an illumination optical system for illuminating a reticle with illuminating light from a light source, a projection optical system for projecting a pattern, which has been formed on the reticle, onto a photosensitive substrate, a holding unit for holding the reticle, a reticle transport system for transporting the reticle, a substrate stage capable of holding and moving the substrate, and a substrate transport system for transporting the substrate. Further, at least one of a pair of the reticle transport system and the holding unit and a pair of the substrate transport system and the substrate stage is accommodated in a partitioned circulation space in which inert gas is filled and the inert gas is circulated by a circulating system having a temperature control mechanism. --

Column 1,

Line 47, "also demand" should read -- also a demand --.

Line 48, "especially" should read -- especially, --.

Line 49, "of" should read -- having a -- and "wavelength 157.6 nm." should read -- wavelength of 157.6 nm.

Line 60, "of" should read -- having a -- and "wavelength 200 nm" should read -- wavelength of 200 nm --

Line 61, "of oscillation" should read -- of the oscillation --.

Line 63, "project" should read -- to project --.

Column 2,

Line 4, "aberration" should read -- aberrations --.

Line 16, "quality" should read -- quantity --.

Line 21, "position" should read -- positions --.

Line 29, "reflection-refraction-type" should read -- a reflection-refraction-type --.

Line 31, "of refraction" should read -- of a refraction --.

Line 32, "telecentrically" should read -- telecentrically, --.

Line 61, "improvement alignment" should read -- improvement in alignment --.

Column 3,

Line 10, "(Though" should read -- (Through --.

Line 14, "of line" should read -- of a line --.

Line 22, "is small" should read -- is a small --.

Line 23, "made short-" should read -- made to be short- --.

Line 29, "'Off-axis" should read -- an "Off-axis --.

Line 37, "from resist" should read -- from a resist --.

Line 42, "where" should read -- wherein --.

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Column 4,

Line 56, "(X5-BL-XP) or (X5-BL+XP)" should read -- (XS-BL-XP) or (X5-BL+XP). --.

Line 63, "accurate" should read -- accurately --.

Line 66, "actuality" should read -- actuality, --.

Column 6,

Line 11, "distance" should read -- the distance --.

Line 27, "or ArF" should read -- or an ArF --.

Line 34, "where" should read -- wherein --.

Line 47, "prior-art" should read -- prior art --.

Column 7,

Line 27, "where" should read -- wherein --.

Column 8,

Line 29, "for various" should read -- for performing various --.

Column 10,

Line 47, "details the" should read -- details of the --.

Line 60, "wavelength 157.6 nm)" should read -- wavelength of 157.6 nm) --.

Column 11,

Line 18, "of measurement." should read -- of the measurement. --.

Line 42, "measurement." should read -- the measurement. --.

Column 12,

Line 12, "where" should read -- wherein --.

Line 17, "to position" should read -- to the position --.

Line 20, "optic" should read -- optical --.

Line 23, "Thus" should read -- Thus, --.

Line 40, "opposite the" should read -- opposite to the --.

Line 57, "in highly" should read -- in a highly --

Column 13,

Line 3, "where" should read -- wherein --.

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Column 14,

Line 10, "stage **26**" should read -- stage **26**, --.
Line 17, "this" should read -- the --.
Line 27, "and lower" should read -- and to lower --.
Line 32, "preferably" should read -- preferably, --.
Line 41, "In case" should read -- In the case --.
Line 55, "and lower" should read -- and to lower --.

Column 15,

Line 58, "where" should read -- wherein --.

Column 16,

Line 62, "spaces **69, 70**" should read -- spaces **69, 70**, --.

Column 17,

Line 3, "spaces therefore" should read -- spaces, therefore, --.
Line 53, "FIG. **9B**." should read -- FIG. **9B**, --.
Line 56, "opposite the" should read -- opposite to the --.
Line 62, "namely" should read -- namely, --.

Column 18,

Line 42, "opposite the" should read -- opposite to the --.
Line 52, "that **LW2**" should read -- that length **LW2** --.

Column 19,

Line 33, "space" should read -- the space --.
Line 49, "of large" should read -- of a large --.
Line 59, "of Semiconductor" should read -- of a Semiconductor --.
Line 61, "eg., (semiconductor)" should read -- (e.g., semiconductor --.

Column 20,

Line 9, "eg., (lithographic)" should read -- (e.g., lithographic --.
Line 12, "etc.)" should read -- etc.), --.
Line 13, "eg., (assembly)" should read -- (e.g., assembly --.

Column 21,

Line 15, "manufacturing" should read -- the manufacturing -- and "of semiconductor" should read -- of a semiconductor --.
Line 16, "devices)." should read -- device). --.

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Column 21 (cont'd),

Line 27, "maker **210**, resist" should read -- maker **210**, a resist --.
Line 28, "and thin-film" should read -- and a thin-film --.
Line 30, "for remote" should read -- for performing remote --.

Column 22,

Line 2, "vender," should read -- vendor, --.
Line 9, "Manufacturing Semiconductor" should read -- Manufacturing a Semiconductor --.
Line 27, "and durability" should read -- and a durability --.

Column 24,

Line 15, "detections" should read -- detection --.

Signed and Sealed this

Tenth Day of May, 2005

A handwritten signature in black ink, appearing to read "Jon W. Dudas". The signature is stylized with a large, looping initial "J" and a distinct "D" at the end.

JON W. DUDAS
Director of the United States Patent and Trademark Office